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TELECOPY/FACSIMILE COVER LETTER

TO: Office of Initial Patent Examination's
Filing Receipt Corrections

DATE: 6/7/2006

FROM: Mr. Lenin V. Zeledón
Intellectual Property Specialist

TIME: 10:26 AM

TOTAL NO. OF PAGES, INCLUDING COVER: 5

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MESSAGE:

U.S. Patent Application 10/553,272; Our Ref. No.: 89227.0010

Please note the omission on the attached Filing Receipt. The "Applicant's" section, the following names were left out; Toshio YAMANAKA, Yuki TAKIGUCHI, Kaoru NISHIKAWA as it appears on the priority claimed application PCT/JP2004/005273.

Please provide us with the Corrected Filing Receipt as soon as possible.

Thank you.

Enclosure: (Official Filing Receipt, Copy of International WO/2004/092838 page)

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TELECOPY/FAX NUMBER: 1-571-273-8300

CLIENT NUMBER: 89227.0010

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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/553,272	10/12/2005	1712	3350	89227.0010	1	49	1

CONFIRMATION NO. 6639

000026021
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Applicant(s)

Koji Okada, Osaka, JAPAN;
Toshio Yamanaka, Osaka, JAPAN;Power of Attorney: The patent practitioners associated with Customer Number 000026021.

Domestic Priority data as claimed by applicant

This application is a 371 of PCT/JP04/05273 04/13/2004

Foreign Applications

JAPAN 2003-110359 04/15/2003
JAPAN 2003-117947 04/23/2003
JAPAN 2003-124026 04/28/2003
JAPAN 2003-123192 04/28/2003

If Required, Foreign Filing License Granted: 05/30/2006

The country code and number of your priority application, to be used for filing abroad under the Paris Convention, is **US10/553,272**

Projected Publication Date: 09/07/2006

Non-Publication Request: No

Early Publication Request: No

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DOCKETING

Title

Photosensitive resin composition capable of being developed with aqueous developer and photosensitive dry film resist, and use thereof

Preliminary Class

525

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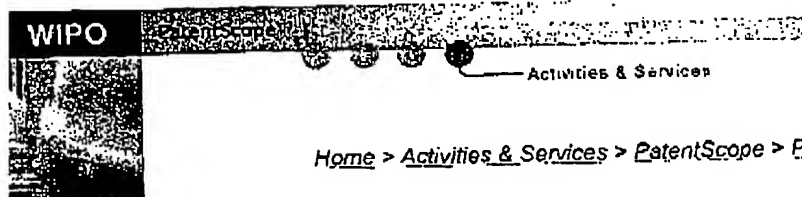
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(WO/2004/092838) PHOTSENSITIVE RESIN COMPOSITION CAPABLE OF BEING DEVELOPED WITH AQUEOUS DEVELOPER AND PHOTSENSITIVE DRY FILM AND USE THEREOF

Biblio. Data Description Claims National Phase Notices Documents

Latest bibliographic data on file with the International Bureau

Publication Number: WO/2004/092838 **International Application No.:** PCT/JP2004/005273
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Priority Data: 2003-110359 15.04.2003 JP
2003-117947 23.04.2003 JP
2003-124026 28.04.2003 JP
2003-123192 28.04.2003 JP

Title: PHOTSENSITIVE RESIN COMPOSITION CAPABLE OF BEING DEVELOPED WITH AQUEOUS DEVELOPER AND PHOTSENSITIVE DRY FILM RESIST, AND USE THEREOF

Abstract: A photosensitive resin composition, which comprises (A) a base resin component being at least 1) a polyimide resin containing at least one of a hydroxyl group and a carboxyl group in the structure thereof, (A-2) a polyamide resin containing at least one of a hydroxyl group and a carboxyl group in the structure thereof, and (A-3) a photosensitive imide (meth)acrylosiloxane oligomer, and (B) a (meth)acrylate compound. The photosensitive resin composition allows the achievement of the following characteristics: (1) the realization and improvement of aqueous development, (2) the improvement of the utility of the developed film, (3) the improvement of physical properties after curing, and (4) the simplification of the structure of a printed wiring board, and accordingly can be suitably used, in particular, for a photo-dry film resist and a laminate, a printed wiring board and the like using the film resist.

Designated States: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, R, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW, African Regional Intellectual Property Org. (ARIPO) (BW, GH, GM, KE, LS, MW, MZ, SD, SL, S, ZM, ZW)
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